L Number	Hits	Search Text	DB	Time stamp
1	494	33/645.ccls.	USPAT	2003/07/02 07:09
2	2131	430/22,311.ccls.	USPAT	2003/07/02 07:09
3	489	356/399.ccls.	USPAT	2003/07/02 07:09
4	0	250/491.2.ccls.	USPAT	2003/07/02 07:09
5	1136		USPAT	2003/07/02 07:10
6	4195	33/645.ccls. 430/22,311.ccls.	USPAT	2003/07/02 07:10
`		356/399.ccls. 250/491.2.ccls.		
		438/706,717,725.ccls.		
7	405	(33/645.ccls. 430/22,311.ccls.	USPAT	2003/07/02 07:11
<i>'</i>		356/399.ccls. 250/491.2.ccls.		
		438/706,717,725.ccls.) and alignment near		İ
		mark\$1		
_	6399	alignment near mark\$1 and semiconductor	USPAT;	2003/07/02 07:09
	0000		US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	1787	(alignment near mark\$1 and semiconductor)	USPAT;	2003/06/17 08:02
_	1707	and photoresist	US-PGPUB;	
		dia photororo	EPO; JPO;	
			DERWENT	
i	559	expose\$3 near7 (alignment near mark\$1) and	USPAT;	2003/06/17 08:07
-	333	semiconductor	US-PGPUB;	
		Semiconductor	EPO; JPO;	
			DERWENT	
	1 4 0 7	expos\$3 near7 (alignment near mark\$1) and	USPAT;	2003/06/17 08:07
-	1427	semiconductor	US-PGPUB;	
		Semiconductor	EPO; JPO;	
			DERWENT	
	1010	expos\$3 near5 (alignment near mark\$1) and	USPAT;	2003/06/17 08:07
-	1210	semiconductor	US-PGPUB;	
		semiconductor	EPO; JPO;	
			DERWENT	
		(expos\$3 near5 (alignment near mark\$1) and	USPAT;	2003/06/17 09:07
-	471	(exposs3 nears (alignment hear markyr) and	US-PGPUB;	2000,00,
		semiconductor) and photoresist	EPO; JPO;	
			DERWENT	
_		5 ( 1' manufacture manufacture and	USPAT;	2003/06/17 08:08
	146		US-PGPUB;	2003/00/1/0010
		semiconductor	EPO; JPO;	
			DERWENT	
			USPAT;	2003/06/17 08:0
-	69	(clear\$3 near5 (alignment near mark\$1) and	US-PGPUB;	2003/00/17 00:0
		semiconductor) and photoresist		
			EPO; JPO;	
		101)	DERWENT	2003/06/17 08:1
-	77	(clear\$3 near5 (alignment near mark\$1) and	USPAT;	2003/00/1/ 00:1
		semiconductor) not ((clear\$3 near5	US-PGPUB;	
		(alignment near mark\$1) and semiconductor)	EPO; JPO;	
		and photoresist)	DERWENT	2003/06/17 08:1
_	0	chung near chieh and aligment near mark\$1	USPAT;	2003/00/1/ 00:1
			US-PGPUB;	
			EPO; JPO;	
_		101	DERWENT	2002/06/17 09-1
	0	chuang near chieh and aligment near mark\$1	USPAT;	2003/06/17 08:1
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/06/17 00:1
_	1	chuang near chieh and alignment near	USPAT;	2003/06/17 08:1
		mark\$1	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	249	lin and alignment near mark\$1	USPAT;	2003/06/17 08:1
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	121	(lin and alignment near mark\$1) and	USPAT;	2003/06/17 08:1
		photoresist	US-PGPUB;	
		F	EPO; JPO;	
			DERWENT	
				2003/06/17 08:4

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		"5911108"   "5946583"   "5950093"		
		"5982044").PN.	1	
	435	1 401	USPAT;	2003/06/17 09:08
_	433	and semiconductor) and photoresist) not	US-PGPUB;	
	1	(clear\$3 near5 (alignment near mark\$1) and	EPO; JPO;	
			DERWENT	
		semiconductor)	USPAT	2003/06/23 13:26
_	13		USPAI	2003/00/23 13.20
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		or ("5946583") or ("5627110") or		
ļ		("5316966") or ("5902707") or		
		("5705320")).PN.		

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